



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application of:

Sang-In Lee, et al.

Serial No. **10/525,122**

Filed: **March 20, 2006**

For: **Atomic Layer Deposition of High-k
Metal Silicates**

Examiner: **Roman, Angel**

Art Unit: **2812**

Confirmation No.: **2947**

Atty. Docket No.: **067538-5171-US**

RESPONSE/AMENDMENT

Mail Stop AMENDMENT
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

In response to the non-final Office Action mailed May 7, 2007, please consider the following proposed amendments to the above-identified application and the remarks herein. Please amend the application as follows.

Amendments to the Specification begins on page 2 of this Amendment.

Amendments to the Claims begin on page 3 of this Amendment.

Remarks begin on page 8 of this Amendment.